ION BEAM DEPOSITION SYSTEM ION BEAM DEPOSITION (IBD) ION BEAM ASSISTED DEPOSITION (IBAD)

STANDARD FEATURES:

Electro-Polished Stainless Steel Chamber D-Shaped Box)

4" Diameter View Port on Front Door with Manual Shutter

Turbo Molecular Vacuum Pumping System with Matching Dual Stage Rotary Vane Pump

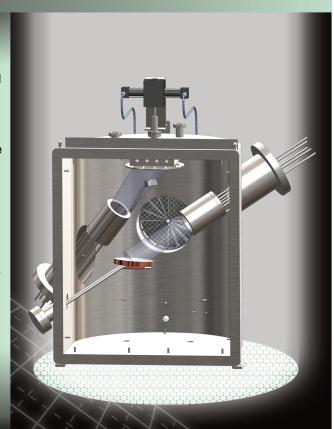
Ion Beam Deposition with Convergent Beam Ion Source & Power Supply, with Easy Target Mounting Assembly

Ion Beam Assisted Deposition with Divergent Beam Ion Source & Power Supply

Quartz Crystal Thickness Sensor with Deposition Controller

Mass Flow Controller with Digital Readout

Full Range Vacuum Gauge with Digital Display & Readout PLC Controlled System



Water Chiller
Load Lock System with Sample
Transfer Adaptability
Multi-Axis Substrate Stage Rotation
Quartz Lamp Heater
(from 300° C up to 800° C)
Planetary Substrate Stage
PC Controlled System

Water Cooled Substrate Stage

Adjustable Size & Height Available for Substrate Stage SQC 310 Film Thickness Monitor & Deposition Controller Motorized Shutter Assembly Dry Scroll Pump Cryo Pumping System Cold Cathode or Hot Cathode Ionization Gauge Additional Spare Flanges for Future Upgrades RF Cleaning/Biasing Capability In Situ Mask Changer



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1 Torr = 1 mm Ha

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